

ABSTRACT OF THE DISCLOSURE

A pattern forming method comprises forming a  
photosensitive resin film on a substrate, exposing the  
photosensitive resin film, forming a pattern of the  
5 photosensitive resin film by supplying a developing  
solution to the photosensitive resin film, and slimming  
to remove a surface layer of the pattern by causing the  
pattern to contact with an activated water.